

PATENT  
81877.0012

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of  
Seiyo Nakashima et al.  
Serial No: 09/816,643  
Filed: March 23, 2001  
For: SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING METHOD

Art Unit: 1763  
Examiner: Kackar, Ram N

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AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated September 9, 2002, please amend the above-referenced application as follows:

IN THE SPECIFICATION:

Please replace the section of the specification entitled **SUMMARY OF THE INVENTION** starting on page 3, line 5, and continuing through page 6, line 23, with the following text:

**"SUMMARY OF THE INVENTION"**

According to a first aspect of the present invention, there is provided a substrate processing apparatus, including:

a processing chamber;  
a susceptor on which a substrate is placed; and  
a heating unit disposed below the susceptor for heating the substrate placed on the susceptor, wherein

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